

Dr. Chaeseon Hong is a dedicated researcher with extensive experience in materials science and semiconductor engineering. Hong recently worked at industry company, where he contributed to cutting-edge projects in display technologies. After earning a Ph.D's degree from Yonsei University in 2023, he pursued advanced research, focusing on oxide semiconductors and next-generation electronic devices.

In Jan 2025, Dr. Hong joined Prof. Aaron Thean's group at NUS as a Research Fellow. His primary focus is developing back-end-of-line (BEOL) compatible processes for oxide FETs, addressing stability issues in FerroFET stacking using low-temperature HZO, and advancing the development of p-type oxide semiconductors for CMOS applications.

With a strong commitment to innovation and a track record of impactful research, Dr. Hong is passionate about solving critical challenges in the semiconductor industry and contributing to the advancement of future electronic devices.

